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PPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO
10/643,597	08/19/2003	Walter H. Whitlock	M02A454	3964
20411 7	590 01/12/2006		EXAMINER	
THE BOC GROUP, INC. 575 MOUNTAIN AVENUE			EL ARINI, ZEINAB	
MURRAY HILL, NJ 07974-2064			ART UNIT	PAPER NUMBER
	•		1746	

DATE MAILED: 01/12/2006

Please find below and/or attached an Office communication concerning this application or proceeding.

		Application No.	Applicant(s)			
Office Action Summary		10/643,597	WHITLOCK, WAI	WHITLOCK, WALTER H.		
		Examiner	Art Unit			
		Zeinab E. EL-Arini	1746			
Period fo	The MAILING DATE of this communication app or Reply	ears on the cover she	et with the correspondence ac	ddress		
WHIC - Exter after - If NO - Failu Any r	ORTENED STATUTORY PERIOD FOR REPLY CHEVER IS LONGER, FROM THE MAILING DATE in a solid part of time may be available under the provisions of 37 CFR 1.13 SIX (6) MONTHS from the mailing date of this communication. In period for reply is specified above, the maximum statutory period were to reply within the set or extended period for reply will, by statute, reply received by the Office later than three months after the mailing and patent term adjustment. See 37 CFR 1.704(b).	ATE OF THIS COMMI 36(a). In no event, however, m vill apply and will expire SIX (6) cause the application to becor	UNICATION. ay a reply be timely filed MONTHS from the mailing date of this one ABANDONED (35 U.S.C. § 133).			
Status						
2a)⊠	<i>'</i> —	action is non-final.	•	e merits is		
Dispositi	on of Claims					
5)□ 6)⊠ 7)□	Claim(s) 1-20 is/are pending in the application. 4a) Of the above claim(s) is/are withdray Claim(s) is/are allowed. Claim(s) 1-20 is/are rejected. Claim(s) is/are objected to. Claim(s) are subject to restriction and/or	vn from consideration				
Applicati	on Papers					
10)	The specification is objected to by the Examine. The drawing(s) filed on is/are: a) acce Applicant may not request that any objection to the o Replacement drawing sheet(s) including the correct The oath or declaration is objected to by the Ex	epted or b) objected drawing(s) be held in ab- ion is required if the draw	eyance. See 37 CFR 1.85(a). ving(s) is objected to. See 37 C			
Priority u	ınder 35 U.S.C. § 119					
 12) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f). a) All b) Some * c) None of: 1. Certified copies of the priority documents have been received. 2. Certified copies of the priority documents have been received in Application No 3. Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)). * See the attached detailed Office action for a list of the certified copies not received. 						
2) Notice 3) Inform	e of References Cited (PTO-892) e of Draftsperson's Patent Drawing Review (PTO-948) nation Disclosure Statement(s) (PTO-1449 or PTO/SB/08) r No(s)/Mail Date 08/25/05.	Paper	lew Summary (PTO-413) No(s)/Mail Date of Informal Patent Application (PTo	O-152)		

DETAILED ACTION

The amendment and remarks filed 10/28/05 have been acknowledged and entered.

Specification

The amendment to the specification, filed 10/28/05 is non-compliant amendment, because complete paragraphs including the amendment on pages 4 and 11 have not been provided.

Claim Rejections - 35 USC § 112

- The following is a quotation of the second paragraph of 35 U.S.C. 112:
 The specification shall conclude with one or more claims particularly pointing out and distinctly claiming the subject matter which the applicant regards as his invention.
- 2. Claims 6-7 are rejected under 35 U.S.C. 112, second paragraph, as being indefinite for failing to particularly point out and distinctly claim the subject matter which applicant regards as the invention.

In claims 6, 7, line 2, "the step of contacting", lacks antecedent basis. At line 3, "the steps" lacks antecedent basis.

The 112 rejections stated in paper No. 042505 have been withdrawn in view of applicants' amendment.

Claim Rejections - 35 USC § 103

3. Claims 1-20 are rejected under 35 U.S.C. 103(a) as being unpatentable over DeYoung et al. (US 2002/0112747) in combination with Nishio (6,612,818).

DeYoung et al. disclose a process and apparatus for cleaning a semiconductor wafer using dense phase carbon dioxide. Dense carbon dioxide is stored in a high-

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pressure vessel (I) (50) (at pressure between 300 and 5000 psi), the wafer is loaded into a cleaning chamber (III)(51). Cleaning chamber (III) is pressurized with clean carbon dioxide from either a bulk storage tank through valve (i)(55) or from pressure vessel (I)(50) through valve (a)(56) to a pressure of between 300 psi and 5000 psi. Highly filtered chemical adjuncts are added to the cleaning chamber from adjunct addition module (VI)(61) through valve (b)(62) during addition of dense CO2 or alternatively prior to the addition of dense CO2. The reference discloses conveying a dense gas component and a liquid component to a vessel, applying an elevated pressure to said vessel, and contacting said component with the surface of the wafer. The reference discloses the dense component and the liquid component (isopropyl alcohol), the pressure, and the mixing steps as claimed. See paragraphs 40-41,48-54 and 63, and Fig.4.

DeYoung et al. do not teach using a bellows accumulator as claimed.

Nishio discloses a bellows type pump or accumulator for transporting chemical liquid in various process such as washing surfaces of liquid crystal display devices in semiconductor producing apparatus. See col. 1, lines 14-46, col. 2, lines 6-18.

It would have been obvious for one skilled in the art to use the accumulator taught by Nishio instead of the pressure vessel taught by DeYoung et al. to obtain the claimed process and system, and to improve the cleaning process. This is because both accumulator and pressure vessel used to elevate the pressure of the cleaning component. It would have been obvious for one skilled in the art to adjust the flow rate to obtain the component velocity as claimed.

4. Claims 1-2, 5, 8-19, and 20 are rejected under 35 U.S.C. 103(a) as being unpatentable over Barton (6,085,762) in combination with Nishio.

Barton discloses a process and system for cleaning a surface of a semiconductor wafer. The reference discloses conveying a component comprises a dense gas component, a liquid component, and a mixture thereof to a tank, applying an elevated pressure to said tank, contacting the component with a surface of semiconductor wafer. The reference discloses the dense gas, the mixing process, and the pressure as claimed. See col. 3, lines 39-67, col. 4, lines 51-55, col. 5, lines 18-21, col. 7, lines 46-62, col. 8, lines 2-5, 11-20, 29-54, col. 12, lines 1-15, the claims and Fig. 1.

Barton does not teach the bellows accumulator as claimed.

Nishio as discussed supra discloses the bellows accumulator as claimed.

It would have been obvious for one skilled in the art to use the accumulator taught by Nishio instead of the ballast tank taught by Barton to obtain the claimed process and system, and to improve the cleaning process. Simply alternating choice of tank because Barton discloses that to render the process as continuously efficient as possible by providing a ready source of pressurized fluid at any time needs this.

These rejections stated in paper No. 042505 are maintained.

Response to Arguments

5. Applicant's arguments filed 10/28/05 have been fully considered but they are not persuasive. Applicant's argument with respect to Nishio does not disclose applying an elevated pressure to the bellows is unpersuasive, because one skilled in the art would

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use pressure to discharge the liquid from the bellows towards the surface to be cleaned. It would have been obvious for one skilled in the art to adjust the pressure in Nishio by using pressure regulating mechanism. See Nishio'818, col. 4, lines 5-14, col. 12, lines 22-50. This is also because the pressure as claimed (elevated pressure) could read on pressurizing the bellow to discharge the liquid toward the surface to be treated. This is also because all references are from the same technical endeavor, which is using densified (e.g liquid or supercritical) carbon dioxide cleaning composition for cleaning a surface of a substrate under pressure.

Conclusion

- 6. The prior art made of record and not relied upon is considered pertinent to applicant's disclosure. Nishio et al. (6,604,919) disclose fluid apparatus such as a pump or an accumulator.
- 7. **THIS ACTION IS MADE FINAL.** Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of

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the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the mailing date of this final action.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Zeinab E. EL-Arini whose telephone number is (571) 272-1301. The examiner can normally be reached on Monday-Friday.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Michael Barr can be reached on (571) 272-1414. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Teinal Elanini Zeinab E. EL-Arini Primary Examiner Art Unit 1746

ZEE 01/06/06